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Application Number	10/757,778
Filing Date	January 15, 2003
First Named Inventor	Michael P.C. Watts
Art Unit	Unassigned
Examiner Name	Unassigned
Attorney Docket Number	P80/MII-40-22-03

Total Number of Pages in This Submission

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Forty-eight (48) References
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Remarks

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Firm or Individual name	Law Office of Kenneth C. Brooks
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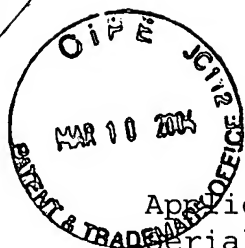
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March 3, 2004

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Watts et al.

PATENT APPLICATION

Serial No.: 10/757,778

Group Art Unit: Unassigned

Filing Date: January 15, 2003

Examiner: Unassigned

For: A METHOD TO IMPROVE THE FLOW RATE OF IMPRINTING MATERIAL

INFORMATION DISCLOSURE STATEMENT

Commissioner

for Patents

Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
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10/191,749	Watts et al.	07/09/2002
10/194,414	Sreenivasan et al.	07/11/2002
10/194,991	Sreenivasan et al.	07/11/2002

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<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
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Chou et al. "Imprint of Sub-25 nm Vias and Trenches in Polymers," *Applied Physics Letters*, 67(21), pp. 3114-3116, 1995.

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Chou. "Nanoimprint Lithography and Lithographically Induced Self-Assembly," *MRS Bulletin*, pp. 512-517, July 2001.

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Respectfully,



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Telephone: 512-527-0104

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patentsrus@earthlink.net

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Application Number	10/757,778
Filing Date	01/15/2004
First Named Inventor	Watts et al.
Group Art Unit	Unassigned
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Attorney Docket Number	P80/MII-40-22-03

U.S. PATENT DOCUMENTS

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First Named Inventor	Watts et al.
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	A30	COWIE, "Polymers: Chemistry and Physics of Modern Materials," 1991, pp. 408-409, 2 nd Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 th Street, NY, NY 10001-2291.	
	A31	KRUG et al., "Fine Patterning of Thin Sol-Gel Films," Journal of Non-Crystalline Solids, 1992, pp. 447-450, vol. 147 & 148.	
	A32	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A33	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A34	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A35	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	A36	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	A37	SCHEER et al., "Problems of the Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3917-3921, vol. B 16(6).	
	A38	XIA et al., "Soft Lithography," Annu. Rev. Mater. Sci., 1998, pp. 153-184, vol. 28.	
	A39	XIA et al., "Soft Lithography," Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.	
	A40	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	

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Sheet	4	of	4	Attorney Docket Number	P80/MII-40-22-03

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	A41	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	A42	CHOU, "Nanoimprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	
	A43	CHOI et al., "High Precision Orientation Alignment and Gap Control Stages for Imprint Lithography Processes," U.S. Patent Application 09/698,317, Filed with USPTO on October 27, 2000..	
	A44	CHOI et al., "Method and System of Automatic Fluid Dispensing for Imprint Lithography Processes," U.S. Patent Application 09/908,455, Filed with USPTO on July 17, 2001.	
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